

In the Abstract:

On Page 47, Line 2, after "filter", please insert -- not only --

On Page 47, Line 2, after "substances", please insert -- but also  
for not generating hazardous contaminates --.

In the Claims:

Please amend the following claims.

In Claim 6, line 2, delete "or 5."

7. (Amended) A method for manufacturing a filter medium for an air filter according to [any one of Claims 4 to 6] Claim 4 wherein said polymer dispersion is obtained by first dissolving said hydrophilic monomer in water, adding said hydrophobic monomer to this solution and dispersing said hydrophobic monomer in said solution, and adding said polymerization initiator to form a copolymer, and wherein volatile organic substances are removed from said polymer dispersion by any one treatment of vacuum suction, aeration, nitrogen purging, and steam injection.

8. (Amended) An air filter comprising:  
a filter medium according to [any one of Claims 1 to 3 or a  
filter medium manufactured by a method according to any one of Claims 4 to  
6] Claim 1; and  
a frame and a sealing material incapable of generating  
gaseous organic substances,  
wherein said air filter is assembled in a space free of  
gaseous organic substances.

A 2

In Claim 11, Line 2, after "trapping", insert -- at least one of --.

In Claim 11, Line 2, delete "and/or" and insert -- and --.

Please add the following new claims:

Sub  
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1 12. (New) A method for manufacturing semiconductors, wherein  
2 a silicon wafer for said semiconductor is processed in at least one of a clean  
3 room and a local facility having an air filter as defined in Claim 8.

1 13. (New) A semiconductor device made by processing a silicon  
2 wafer in at least one of a clean room and a local facility having an air filter as  
3 defined in Claim 8.

1 14 (New) A local facility as defined in Claim 10 which  
2 comprises a clean bench, a clean booth, a wafer stocker, wafer transfer space,  
3 and semiconductor fabrication equipment.

1 15. (New) A local facility as defined in Claim 12 which  
2 comprises a clean bench, a clean booth, a wafer stocker, wafer transfer space,  
3 and semiconductor fabrication equipment

1 16. (New) A local facility as defined in Claim 13 which  
2 comprises a clean bench, a clean booth, a wafer stocker, wafer transfer space,  
3 and semiconductor fabrication equipment

1 17. (New) An air filter comprising:  
2 a filter medium according to a filter medium manufactured by a  
3 method according to Claim 4; and